

## **LISTING OF THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. **(Cancelled)**

2. **(Cancelled)**

3. **(Currently Amended)** A substrate processing apparatus for processing a substrate with a plurality of processing solutions having different components, comprising:  
a holding element provided on a rotating base, for holding a peripheral portion of a substrate to keep said substrate in a substantially-horizontal position;  
a rotation element for rotating said substrate held by said holding element about an axis along a substantially-vertical direction;  
an atmosphere cutoff plate positioned above said holding element, facing a top surface of said substrate held by said holding element; and  
a splash prevention element for receiving said plurality of processing solutions splashed from said peripheral portion of said substrate held by said holding element,  
wherein said splash prevention element comprises  
a plurality of recovery ducts used for collecting said plurality of processing solutions;  
a plurality of guiding members for forming said plurality of recovery ducts so that a vertical spacing of each opening thereof is not less than a distance between said rotating base and said atmosphere cutoff plate; and  
a selection element for selecting one of said recovery ducts to be used for collecting a processing solution used in a processing for said substrate, to determine a selected recovery duct,  
wherein a level of a top surface of a guiding member used for forming said selected recovery duct is set not lower than a level of a lower surface of said rotating base near an opening of said selected recovery duct; and

The substrate processing apparatus according to claim 2, wherein a level of a top surface of a guiding member used for forming said selected recovery duct is set not higher than a level of a top surface of said atmosphere cutoff plate.

**4. (Currently Amended)** The substrate processing apparatus according to claim 1, 2 or 3, wherein

said selected recovery duct has a shape curving downward, going away from a substrate with a vertical spacing almost equal to a vertical spacing of an opening thereof.

**5. (Currently Amended)** The substrate processing apparatus according to claim 1, 2 or 3, wherein

said selected recovery duct guides one of said plurality of processing solutions downward almost around a substrate.

**6. (Currently Amended)** The substrate processing apparatus according to claim 1, 2 or 3, further comprising

a suck element communicated with said selected recovery duct, for sucking said one of said plurality of processing solutions.

**7. (Currently Amended)** The substrate processing apparatus according to claim 1, 2 or 3, wherein

said rotating base and said atmosphere cutoff plate each have a disk-like shape and respective edge portions thereof facing said plurality of recovery ducts are vertical slide surfaces.

**8. (Currently Amended)** The substrate processing apparatus according to claim 1, 2 or 3, wherein

respective openings of said plurality of recovery ducts which are vertically stacked are disposed at almost the same position in a vertical direction.